



PATENT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Junji FUJIKAWA et al

Art Unit: 1756

S. N. 09/830,598

Examiner: M. K. Rouhanian

International S.N.: PCT/JP00/06038

Filed: April 27, 2001

International Filing Date: 6 September 2000

For: HALFTONE PHASE SHIFT PHOTOMASK,
AND HALFTONE PHASE SHIFT PHOTOMASK
BLANK FOR THE FABRICATION OF THE SAME

R E S P O N S E

Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated September 16, 2002,
for which a 3 month extension of time is requested, to extend the
period for response to Monday, March 17, 2002, please amend the
above-identified application as follows:

In the claims:

Please amend claim 1 by replacing it with the like-numbered
claim hereinbelow. Markups are provided at the end of this
response showing the changes made by the amendment.

A1
1. (Amended) A halftone phase shift photomask, comprising
tantalum as a main metal component on a transparent substrate,
and containing oxygen, carbon and nitrogen, and not containing
silicon, which photomask has a multilayer structure comprising at
least two or more different layers.